PROCESS FOR DEPOSITING A TUNGSTEN-BASED AND/OR MOLYBDENUM-BASED LAYER ON A RIGID SUBSTRATE, AND SUBSTRATE THUS COATED

ABSTRACT

The present invention is directed to a process for depositing at least one layer (3) based on tungsten and/or on molybdenum by chemical vapor deposition on a non-conductive substrate (1), such as glass, ceramic, glass-ceramic, or polymer, which includes providing at least one tungsten- and/or molybdenum-containing precursor in the form of a metal halide and/or of an organometallic compound, and at least one reducing agent, such as hydrogen or silane, to form the at least one metal layer. The present invention also relates to the substrate obtained by the preceding process and its applications, especially for producing a glazing, mirrors, or emissive screens.